

Optics contamination issues in EUV Lithography

Iwao Nishiyama, Semiconductor Leading Edge Technologies, Japan

Abstract

After a brief overview on EUV lithography development in Japan, the author gives a talk about the optics contamination issues in EUVL. The talk will include the following topics:

- Optics contamination in various vacuum conditions
- Contamination control technologies
- Cleaning of mirrors
- Model of contamination growth